Nondisruptive Lithographic Processes on the Nanoscopic Level

Thomas Russell, University of Massachusetts Amherst

Several routes by which block copolymers can be used to produce arrays of nanoscopic elements that have high aspect ratios (ideal for templating and scaffolding) that exhibit long-range order, that give access to multiple length scale structuring, and that are amenable to being biased by macroscopic features placed on a surface will be described.